

Supplementary Information for

**Enhanced the solar-to-hydrogen efficiency for photocatalytic water
splitting based on polarized heterostructure: The role of intrinsic dipole
in heterostructures**

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Table S1 Calculated lattice parameters a_0 and total heights h , bond lengths, and band gap E_g at the PBE level for M_2XY and E_g at the HSE level M_2X_3 monolayers. These values agree well with previous reports.¹⁻⁴

Materials	$a_0(\text{\AA})$	$h(\text{\AA})$	$d_{M-M}(\text{\AA})$	$d_{M-Se}(\text{\AA})$	$d_{M-S}(\text{\AA})$	$d_{M-Te}(\text{\AA})$	E_g (eV)
In ₂ SSe	4.00	5.24	2.77	2.66	2.58	–	1.61
In ₂ STe	4.15	5.32	2.77	–	2.62	2.83	1.08
In ₂ SeTe	4.21	5.45	2.77	2.71	–	2.84	1.19
Ga ₂ SSe	3.72	4.72	2.46	2.47	2.39	–	2.08
Ga ₂ STe	3.90	4.78	2.45	–	2.45	2.64	0.99
Ga ₂ SeTe	3.98	4.88	2.45	2.55	–	2.66	1.29
In ₂ S ₃	3.94	6.44	–	–	–	–	1.94
In ₂ Se ₃	4.11	6.82	–	–	–	–	1.37
In ₂ Te ₃	4.41	7.36	–	–	–	–	1.12
Ga ₂ S ₃	3.65	5.98	–	–	–	–	2.56
Ga ₂ Se ₃	3.84	6.36	–	–	–	–	1.64
Ga ₂ Te ₃	4.16	6.93	–	–	–	–	0.72

Fig. S1. The partial charge analysis of the conduction band minimum (CBM) and valence band maximum (VBM) of M_2XY and M_2X_3 monolayers.

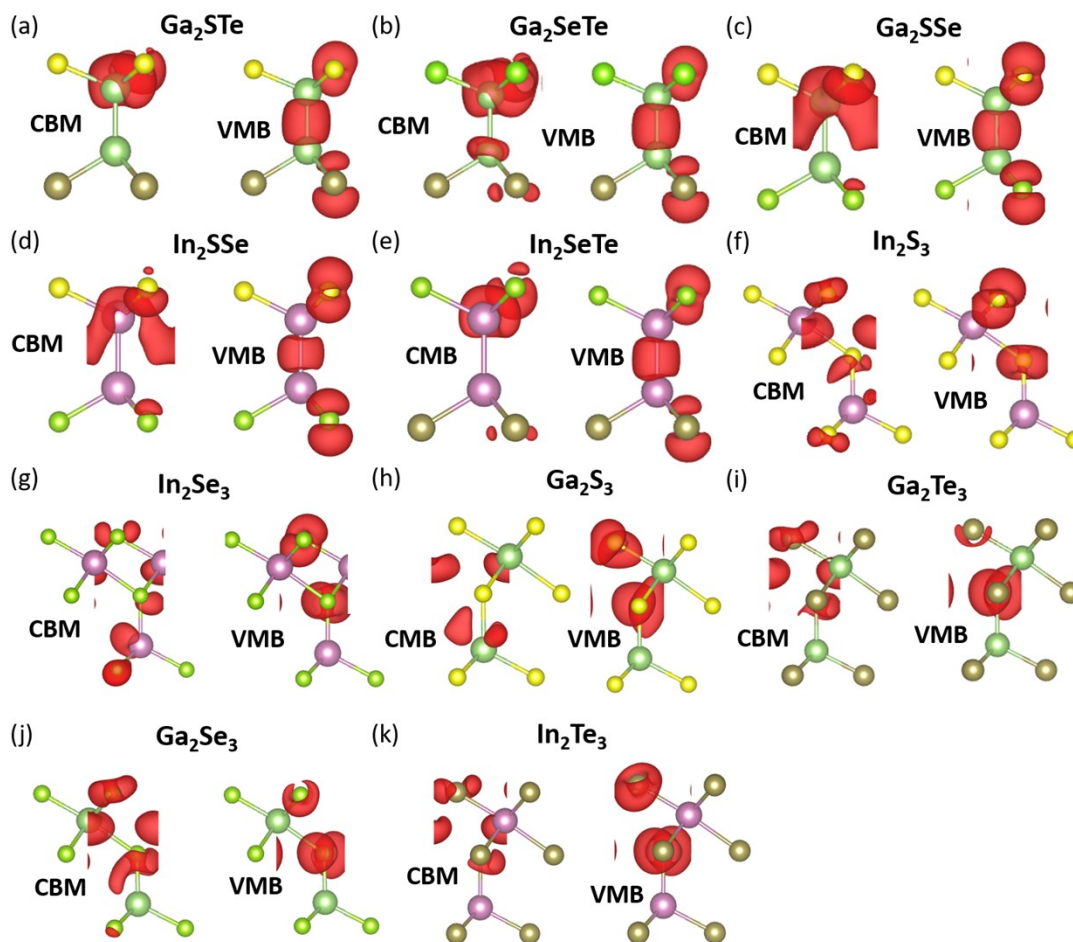


Fig. S2. Top and side views of configurations for vertical M_2XY and M_2X_3 heterostructures with four possible stacking modes.

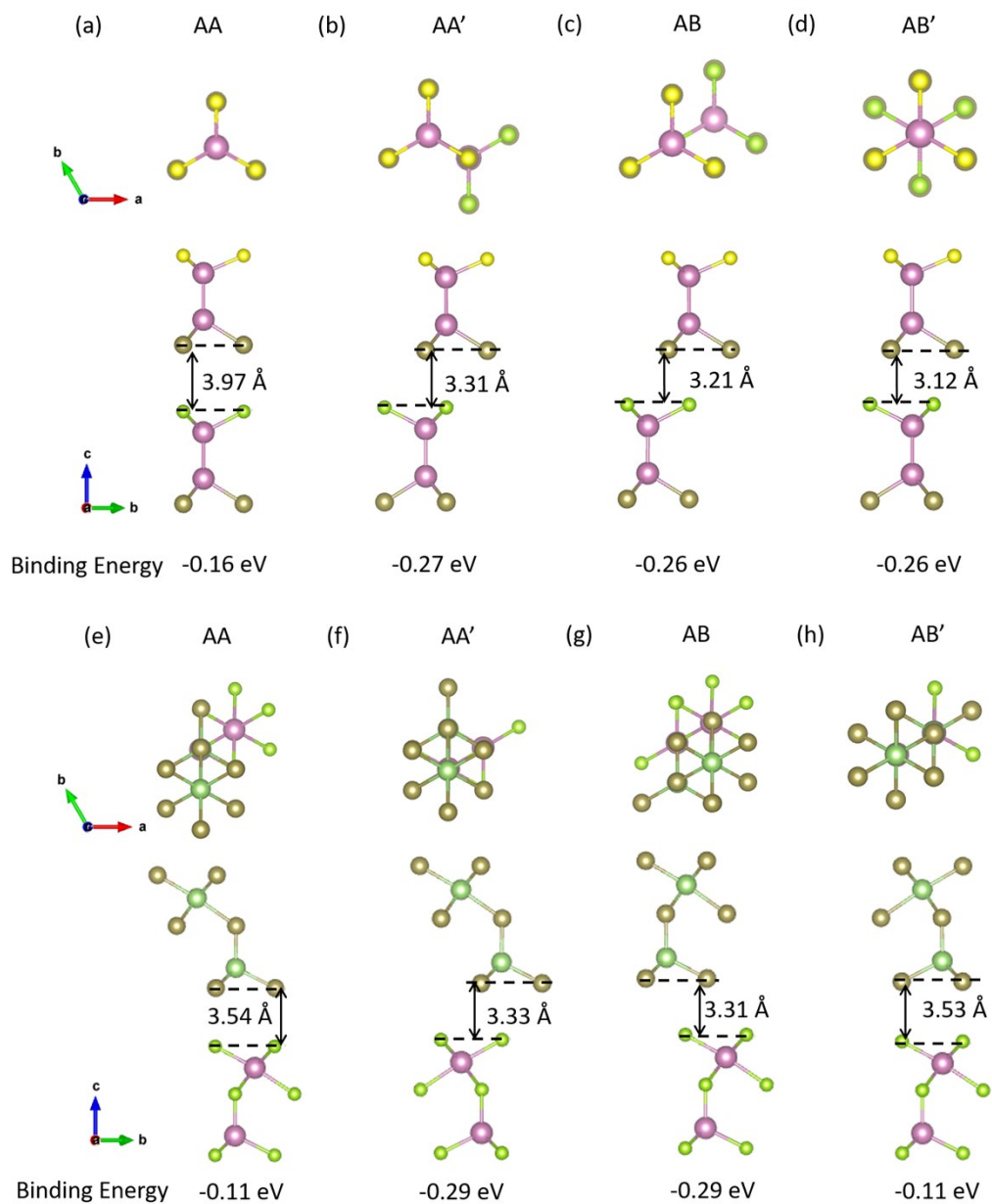


Table S2 Interlayer distance d_l and binding energy E_b of vertical M_2XY and M_2X_3 heterostructures in different types of stacking. The binding energy is calculated by the following formula: $E_b=(E_{\text{hetero}} - E_{L1} - E_{L2})$, where the E_{hetero} , E_{L1} and E_{L2} represent the total energy of heterostructures, and the individual component of single M_2XY and M_2X_3 layers in unit cell, respectively.

Stacking models	AA		AA'		AB		AB'	
	d_l (Å)	E_b (eV)	d_l (Å)	E_b (eV)	d_l (Å)	E_b (eV)	d_l (Å)	E_b (eV)
$\text{Sn}_2\text{Te-SGa}_2\text{Te}$	3.85	-0.17	3.17	-0.25	3.24	-0.24	3.18	-0.25
$\text{SGa}_2\text{Te-Sn}_2\text{Te}$	3.89	-0.16	3.11	-0.25	3.24	-0.24	3.16	-0.25
$\text{Sn}_2\text{Te-SeIn}_2\text{Te}$	3.97	-0.16	3.11	-0.27	3.21	-0.26	3.12	-0.26
$\text{SeIn}_2\text{Te-Sn}_2\text{Te}$	3.92	-0.16	3.27	-0.27	3.26	-0.27	3.10	-0.28
$\text{In}_2\text{Te}_3\text{-Ga}_2\text{Te}_3$	3.58	-0.12	3.35	-0.29	3.33	-0.28	3.58	-0.13
$\text{Ga}_2\text{Te}_3\text{-In}_2\text{Te}_3$	3.57	-0.11	3.33	-0.29	3.37	-0.28	3.57	-0.11
$\text{In}_2\text{Se}_3\text{-In}_2\text{Te}_3$	3.53	-0.10	3.43	-0.28	3.43	-0.28	3.56	-0.11
$\text{In}_2\text{Te}_3\text{-In}_2\text{Se}_3$	3.51	-0.09	3.43	-0.28	3.39	-0.27	3.56	-0.11
$\text{Ga}_2\text{Te}_3\text{-In}_2\text{Se}_3$	3.54	-0.11	3.33	-0.29	3.31	-0.29	3.53	-0.11
$\text{In}_2\text{Se}_3\text{-Ga}_2\text{Te}_3$	3.54	-0.13	3.32	-0.32	3.29	-0.31	3.53	-0.12

Table S3 T The charge transfer Q and internal electric field E_{in} of vertical M_2XY and M_2X_3 heterostructures in different types of stacking.

	$Sn_2Te-SGa_2Te$	SGa_2Te-Sn_2Te	$Sn_2Te-SeIn_2Te$	$SeIn_2Te-Sn_2Te$	$In_2Te_3-Ga_2Te_3$
Q (e)	0.017	0.016	0.017	0.015	0.014
E_{in} (eV)	0.52	0.32	0.45	0.36	0.37
	$Ga_2Te_3-In_2Te_3$	$In_2Se_3-In_2Te_3$	$In_2Te_3-In_2Se_3$	$Ga_2Te_3-In_2Se_3$	$In_2Se_3-Ga_2Te_3$
Q (e)	0.016	0.012	0.023	0.025	0.012
E_{in} (eV)	0.37	0.025	0.58	0.65	0.039

Table S4 The work functions WF (eV) for up and down surfaces of M_2XY , M_2X_3 and InS monolayers.

Surface	In ₂ STe	In ₂ SeTe	Ga ₂ STe	In ₂ Se ₃	In ₂ Te ₃	Ga ₂ Te ₃	InS
up	6.02	4.88	5.72	6.24	5.28	5.32	6.22
down	4.64	4.46	4.96	5.02	4.22	4.43	6.22

Fig. S3. The band alignments of the type-II junction mode for heterostructures Sn_2Te - SeIn_2Te (a) and In_2Se_3 - Ga_2Te_3 (b), respectively. The black arrows represent the charge transfer and e-h recombination process. The plane-average charge density difference $\Delta\rho$ for heterostructures Sn_2Te - SeIn_2Te (c) and In_2Se_3 - Ga_2Te_3 (d). The positive and negative value in $\Delta\rho$ indicate electron accumulation and depletion, respectively. The red (green) colour corresponds to the charge accumulation (depletion). The E_{in} represents the built-in electric field at the interface of heterostructures.

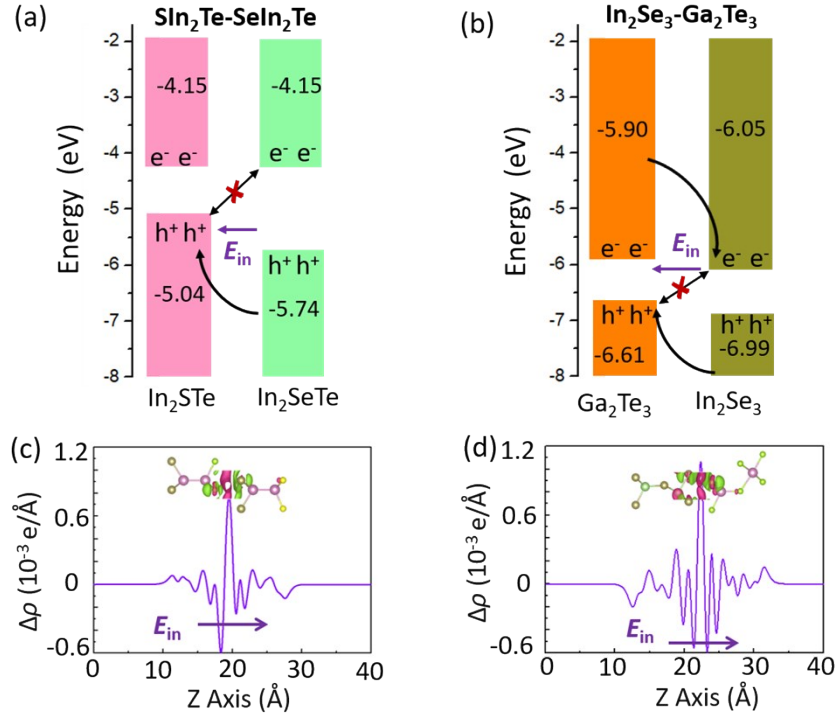


Fig. S4. (a) Plane-average charge density difference $\Delta\rho$ of $\text{In}_2\text{Se}_3/\text{SnP}_3$ heterostructure. The positive and negative value in $\Delta\rho$ indicate electron accumulation and depletion, respectively. The red (green) colour corresponds to the charge accumulation (depletion). (b) The schematic plot of vacuum level for $\text{In}_2\text{Se}_3/\text{SnP}_3$ heterostructure. It is noted that there is a big difference $\Delta\Phi$ for the vacuum level between the SnP_3 surface and In_2Se_3 surface (larger than the intrinsic $\Delta\Phi$ for In_2Se_3 layer), which means that there is an internal electric field pointing to In_2Se_3 layer from SnP_3 layer at the interface of the heterostructure.

